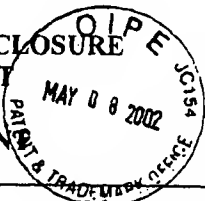


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STATEMENT

BY APPLICANT



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Applicant: Okino et al.

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## U.S. PATENT DOCUMENTS

Init.*	Number	Date	Name	Class	Sub	Filed
<i>38</i>	5,130,213	7/14/1992	Berger et al.			

## FOREIGN PATENT DOCUMENTS

	Number	Date	Country	Class	Sub	

## OTHER DOCUMENTS

<i>30</i>			Koops et al., "Submicron Lithography by Demagnifying Electron-Beam Projection," in Schmahl et al., <i>X-Ray Microscopy, Springer Series in Optical Sciences Vol. 43:118-129</i> , Springer Verlag, Berlin, 1984.

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